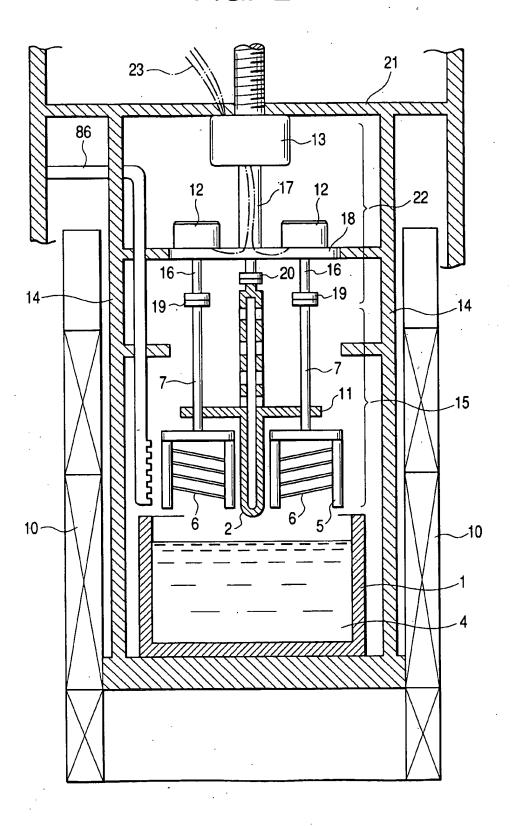
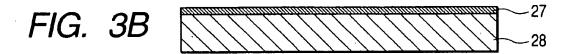
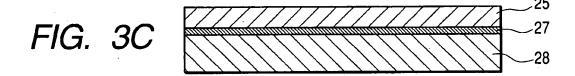


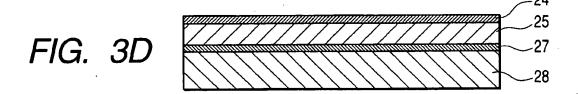
FIG. 2

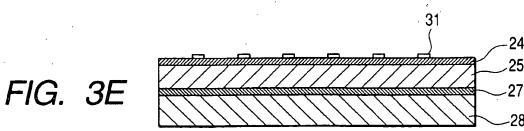


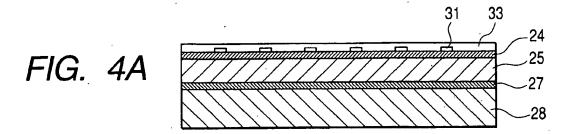


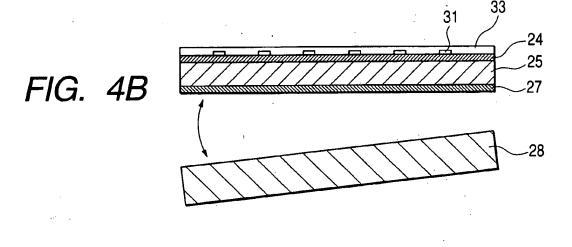


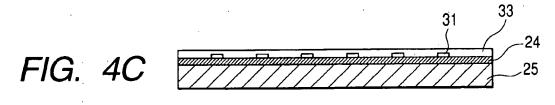












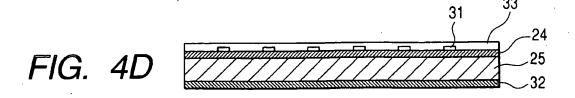


FIG. 5A

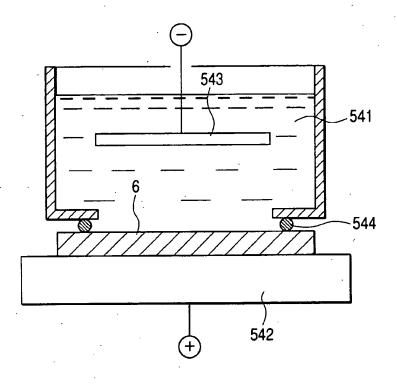


FIG. 5B

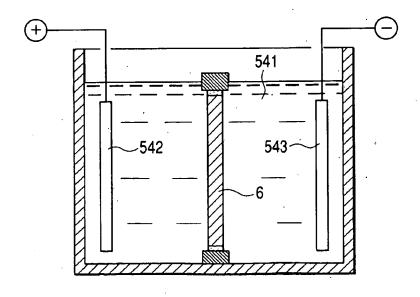
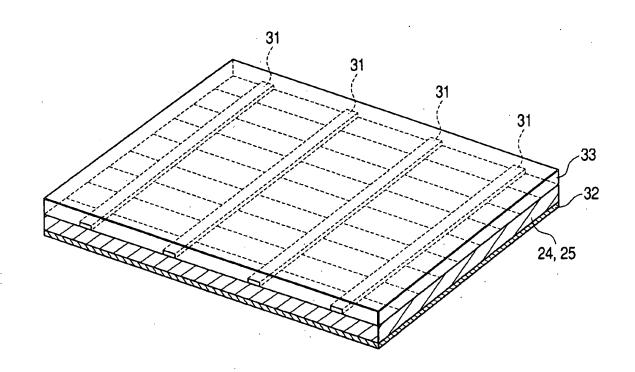
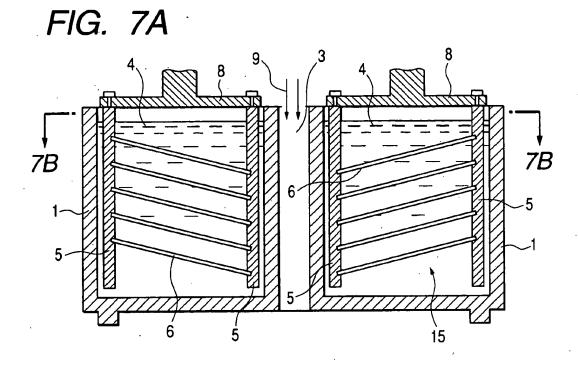


FIG. 6





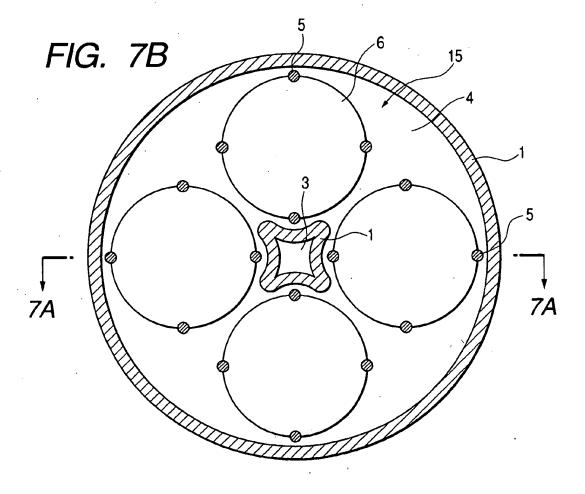
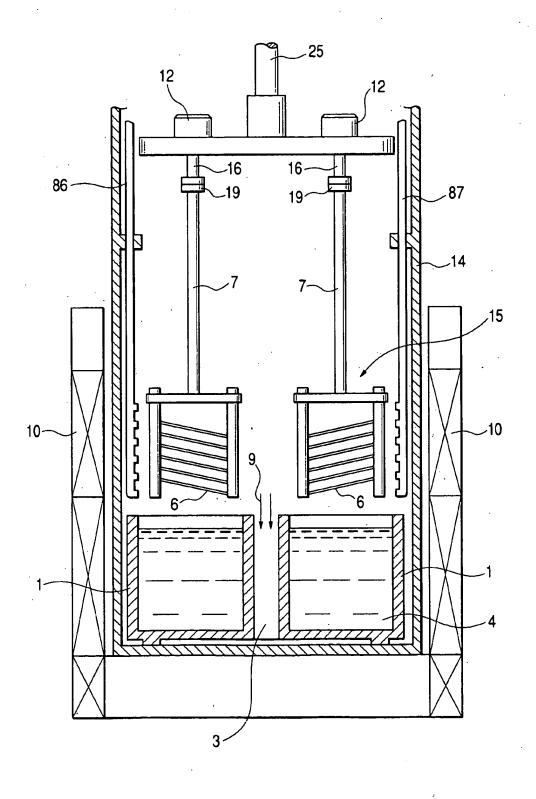
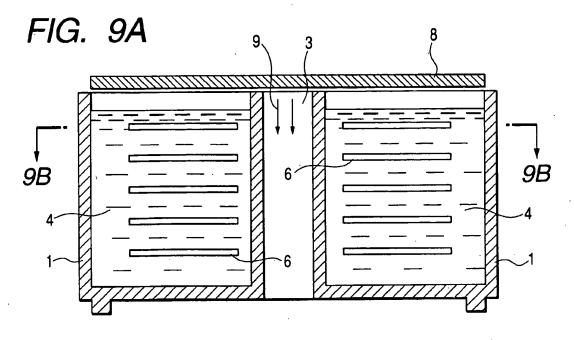
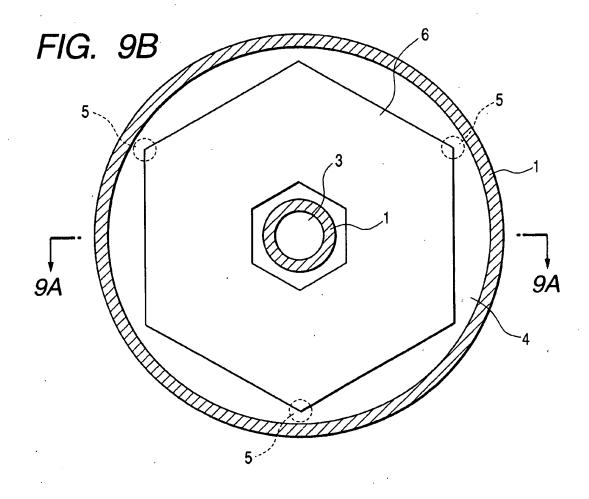


FIG. 8







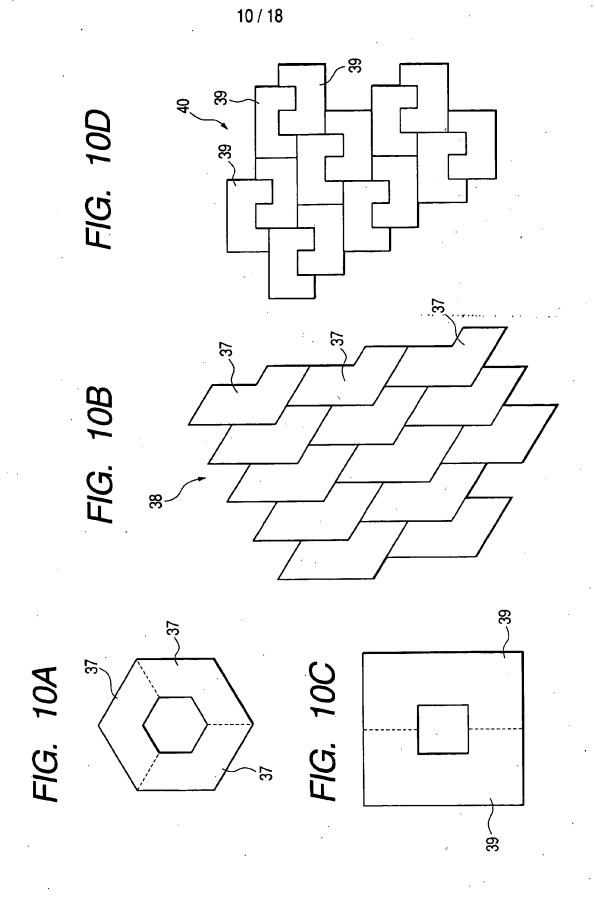


FIG. 11

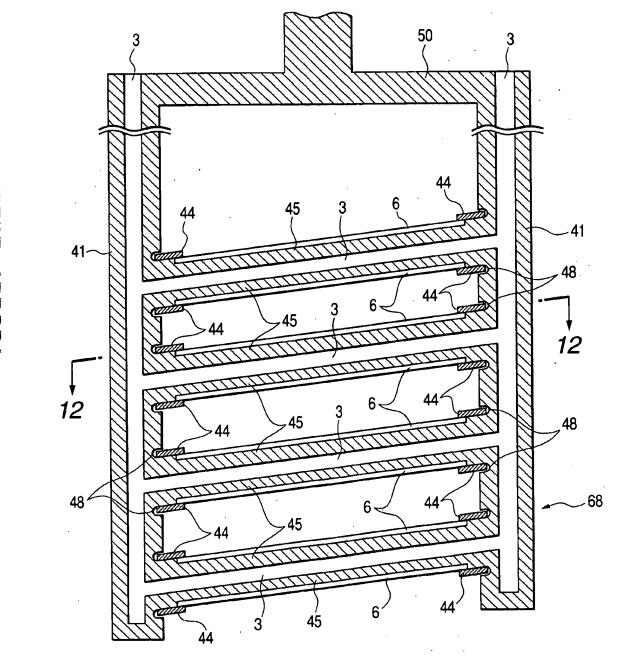
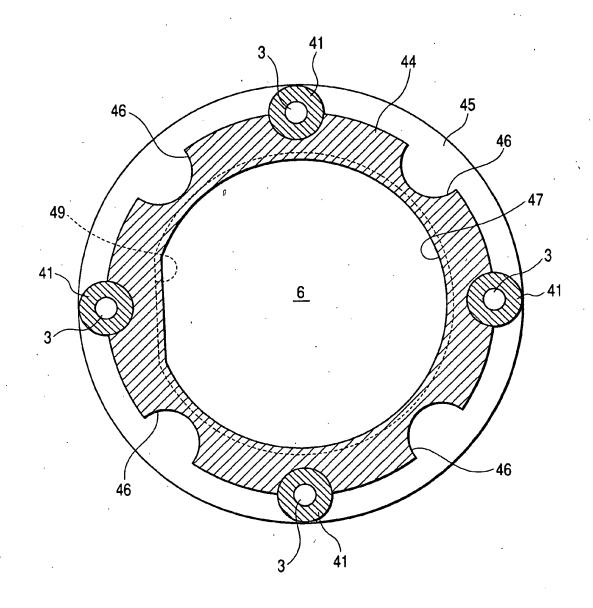
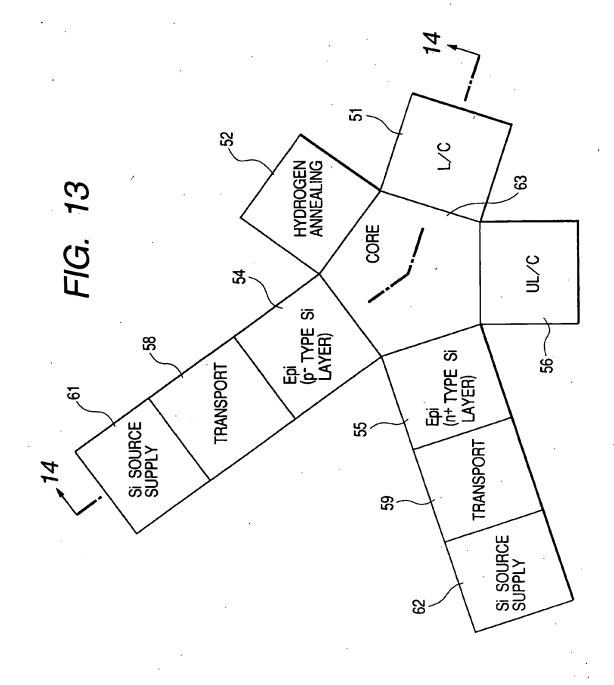
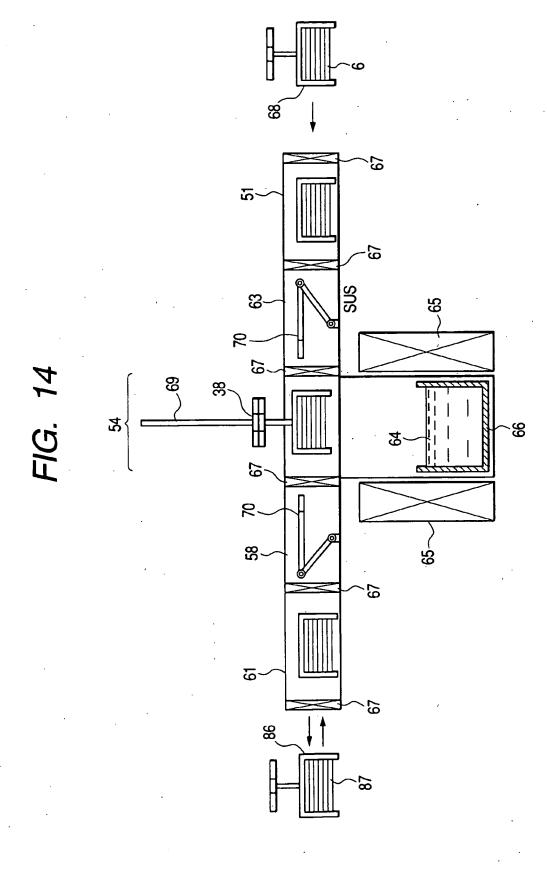


FIG. 12







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SEQUENCE OF DUAL BATH TYPE LIQUID PHASE GROWTH APPARATUS (A:1ST BATCH B:2ND BATCH)

TEMPERATURE RISE 230 **UNLOADING 5** SOURCE SUPPLY 20 190 200 210 220 RETAINING GROWTH 30 UNLOADÍNG 5 COOLING 55 GROWTH Θ 130 140 150 160 170 $\boldsymbol{\omega}$ -ANNEALING 10 TEMPERATURE RISE B RETAINING 10 COOLING 55 ⋖ GROWTH 110 SOURCE SUPPLY 20 × 9 TEMPERATURE RETAINING RISE 8 GROWTH 30 SOURCE SUPPLY 20 Temperature Rise 30 හි TEMPERATURE RISE A LOADING 20 8 2 **ANNEALING 10** 20 RETAINING 10 8 SOURCE SUPPLY 20 Þ 3 TEMPERATURE RISE 30 LOADING 20 20 2 HYDROGEN ANNEALING Epi (n⁺LAYER) Epi (p⁻LAYER) TIME (min)

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FIG. 16

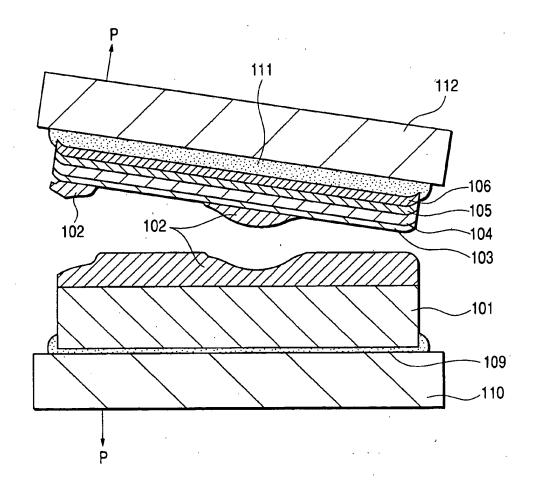
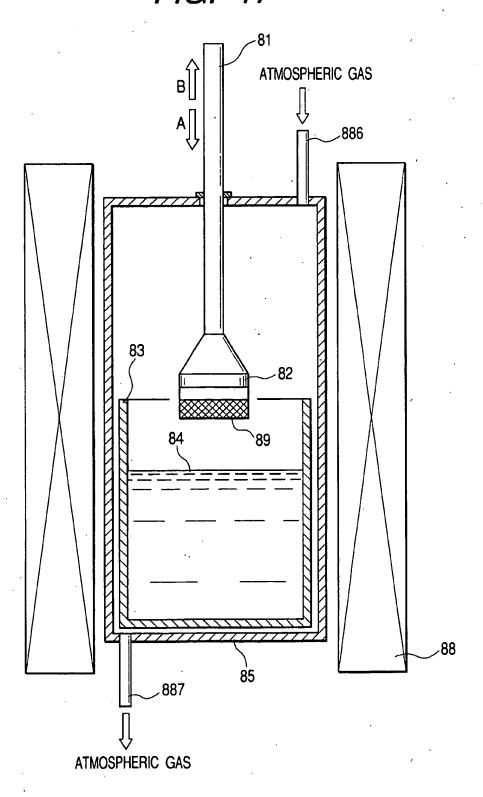


FIG. 17



ACCEPTATE AREAGE



FIG. 18B

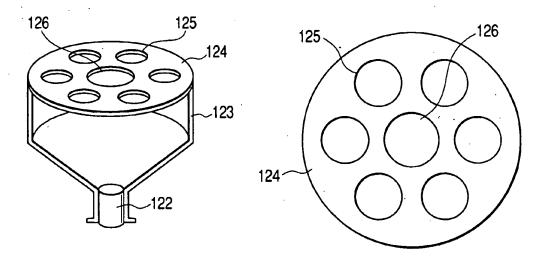


FIG. 18C

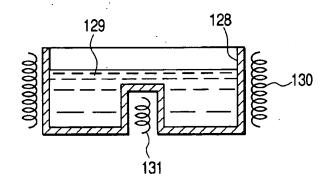


FIG. 19

